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Wide Bandgap Semiconductor Detectors for Harsh Radiation Environments

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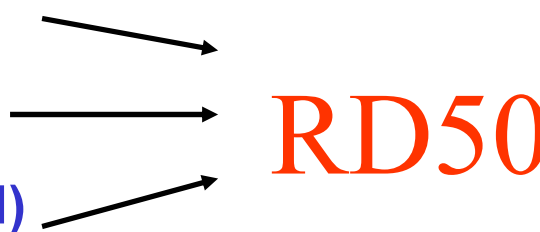
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Outline

- Background and motivation
- Materials investigated
- Fabrication steps (brief)
- Characterisation of detectors
- SiC irradiations, results and analysis
- GaN irradiations, results and analysis
- Conclusions

Background and Motivation

- Stable operation of detector with current Si detector technology not possible beyond fluences of 3×10^{14} fast hadrons/cm²
 - LHC at CERN fluences of $\sim 3 \times 10^{15}$ /cm²
 - sLHC (2012) fluences of $\sim 1.6 \times 10^{16}$ /cm²
 - Number of strategies possible for improving radiation tolerance of systems placed in harsh radiation environments
 - Si with enhanced levels of oxygen
 - 3D detectors
 - **Wide bandgap materials (SiC/GaN)**
- 
- RD50

s/c Material Investigated

➤ *SiC*

- Vanadium doped 4-H SiC (Cree)

Vanadium concentration $\sim 10^{18}\text{cm}^{-3} \Rightarrow \rho \sim 10^{11}\Omega\text{cm}$

- Okmetic Semi-Insulating (SI) 4-H SiC (no vanadium doping)

SI \Rightarrow Highly resistive

➤ *GaN*

- eptiaxial SI (2 μm active region) grown by MOCVD
- Bulk GaN – RARE! (low resistivity $\sim 16\Omega\text{cm}$)

Characterisation

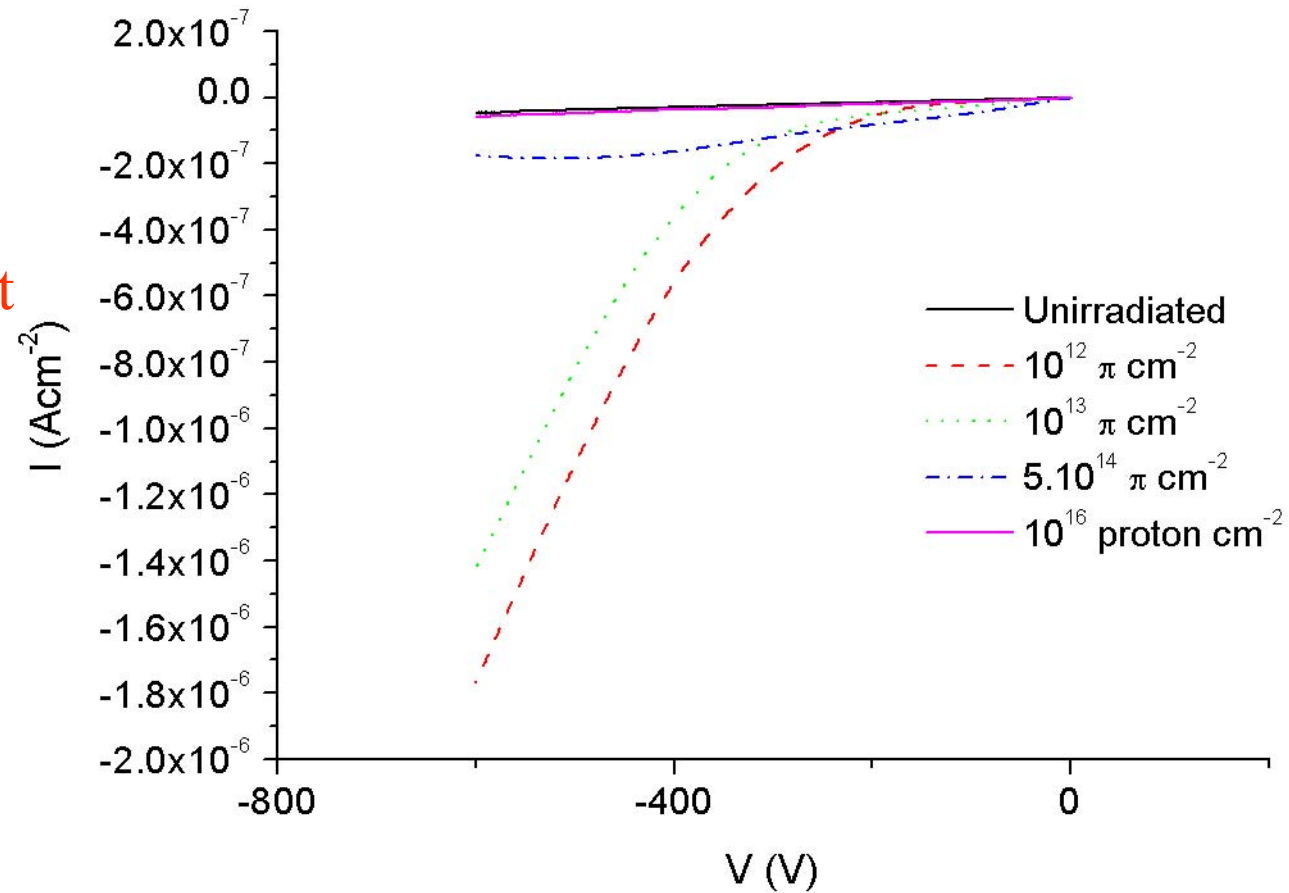
- I – V measurements of detector pre/post irradiations
- Charge Collection Efficiency (CCE) measurements using 5.48 MeV α source
 - measurements done in vacuum (<20 mbar)
 - calibration carried out with Si reference diode

SiC Irradiations

- Vanadium doped SiC irradiated with:
 - 300MeV/c pions at the Paul Scherrer Institut
 - Fluences of $10^{12} \pi\text{cm}^{-2}$, $10^{13} \pi\text{cm}^{-2}$, $5 \times 10^{14} \pi\text{cm}^{-2}$
 - 24GeV/c protons at CERN
 - Fluence of 10^{16}p cm^{-2}
- Non-Vanadium doped SI Okmetic SiC detectors not yet been irradiated

SiC I-V's and CCE's

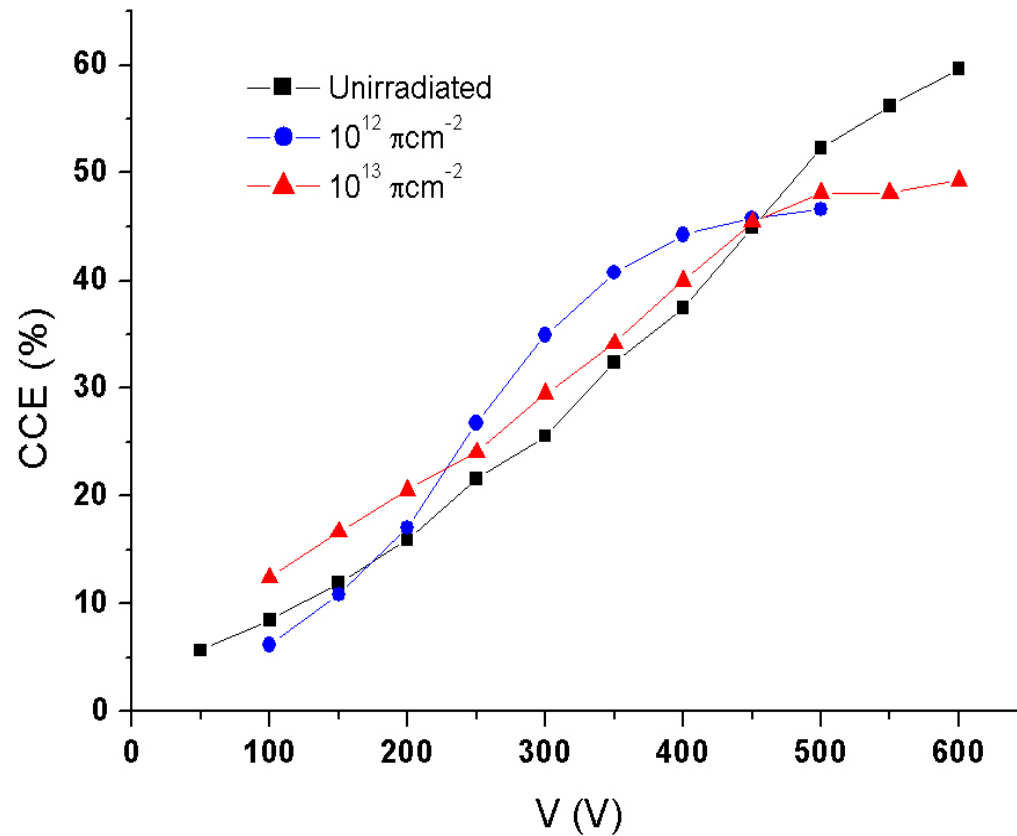
Comparisons of
I-V measurement
For irradiated
Cree
V doped SiC



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SiC CCE



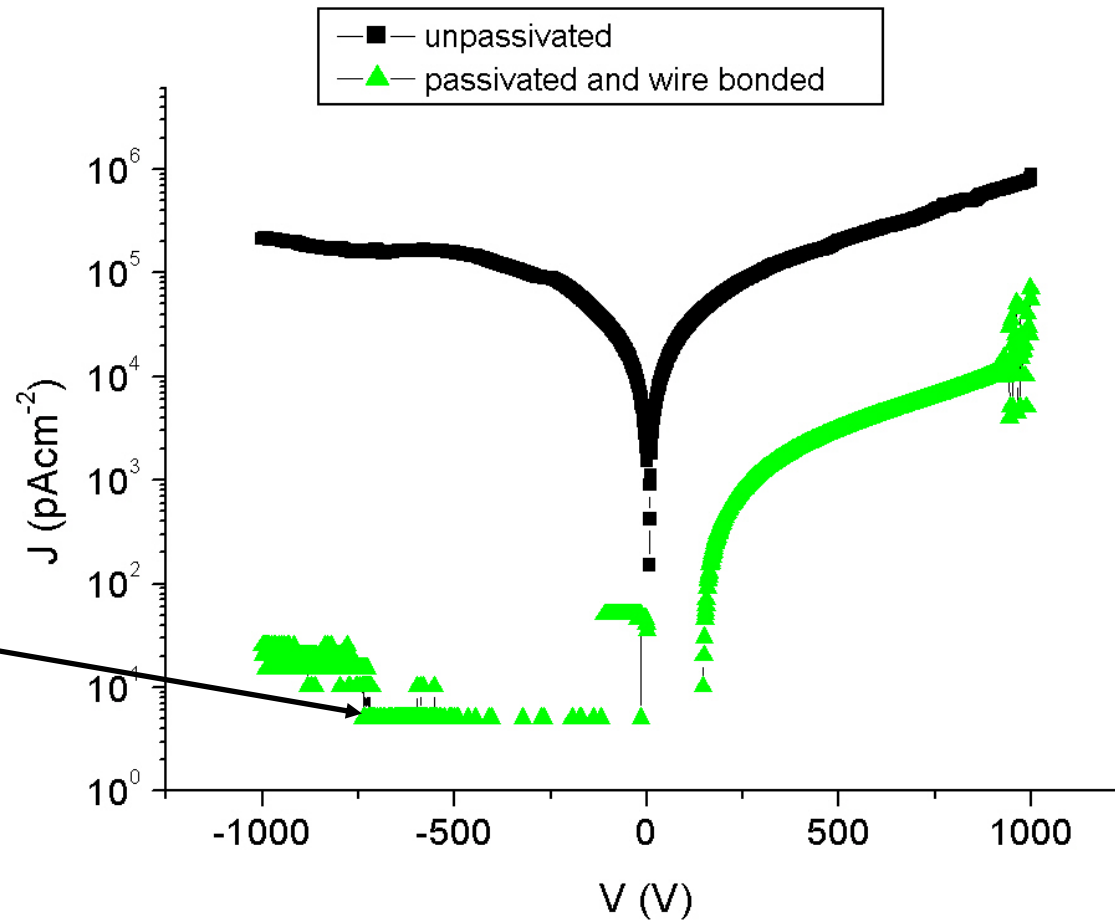
➤ No CCE for $5 \times 10^{14} \text{ cm}^{-2}$
No CCE for 10^{16} cm^{-2}
(wasn't bonded up)

➤ Non Vanadium doped
initial CCE
measurements $\sim 100\%$.

J – V of Okmetic Non V Doped SiC

Current density measurements of diodes fabricated on Okmetic S.I. SiC

Measurement limit of Keithley 237 SMU $\sim 10^{-14}$ A



SiC Analysis and Summary

- High resistivity gives low leakage current
- V dopant reduces maximum CCE due to trapping effects
- Has good radiation hard properties compared to GaAs and Si
 - SiC CCE reduced 15% after pion irradiation
 - GaAs CCE reduced 50% after similar dose
 - Si CCE reduced 30% after similar dose

Important point:

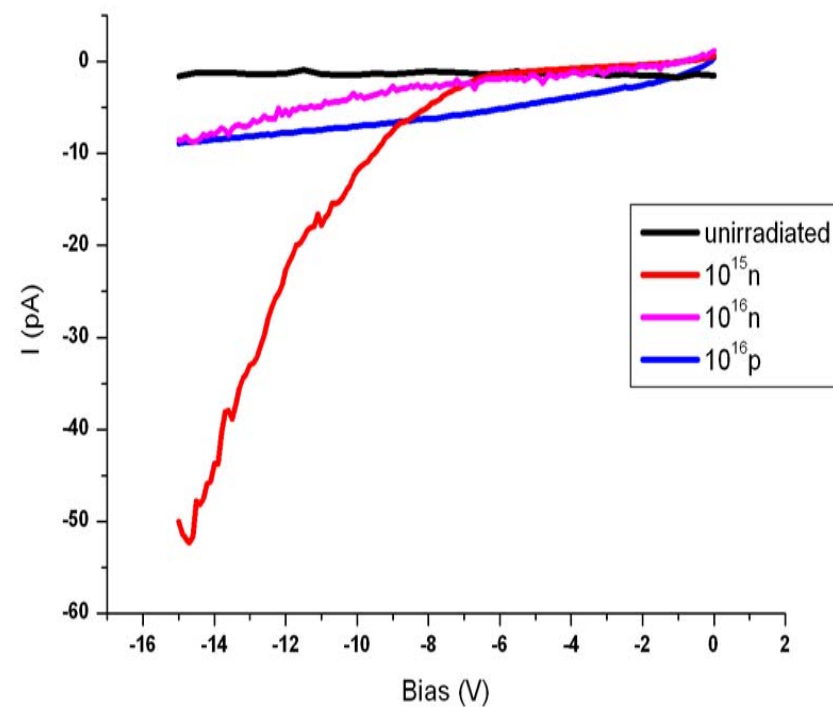
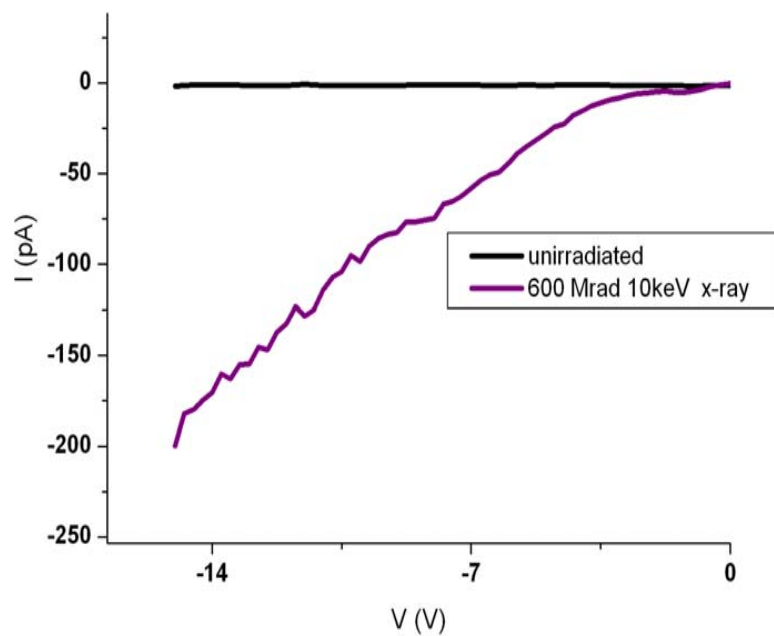
Changes in CCE are for operation under constant bias conditions

GaN Irradiations

- SI epitaxial GaN irradiated with:
 - 10keV X-Rays up to a dose of 600MRad at Imperial College
 - Neutrons at Ljubljana, Slovenia
 - Neutron fluences of 10^{14}ncm^{-2} , 10^{15}ncm^{-2} and 10^{16}ncm^{-2}
 - 24GeV/c protons at CERN at a fluence of 10^{16}pcm^{-2}

- Bulk GaN devices yet to be irradiated

I-V's of SI epitaxial GaN

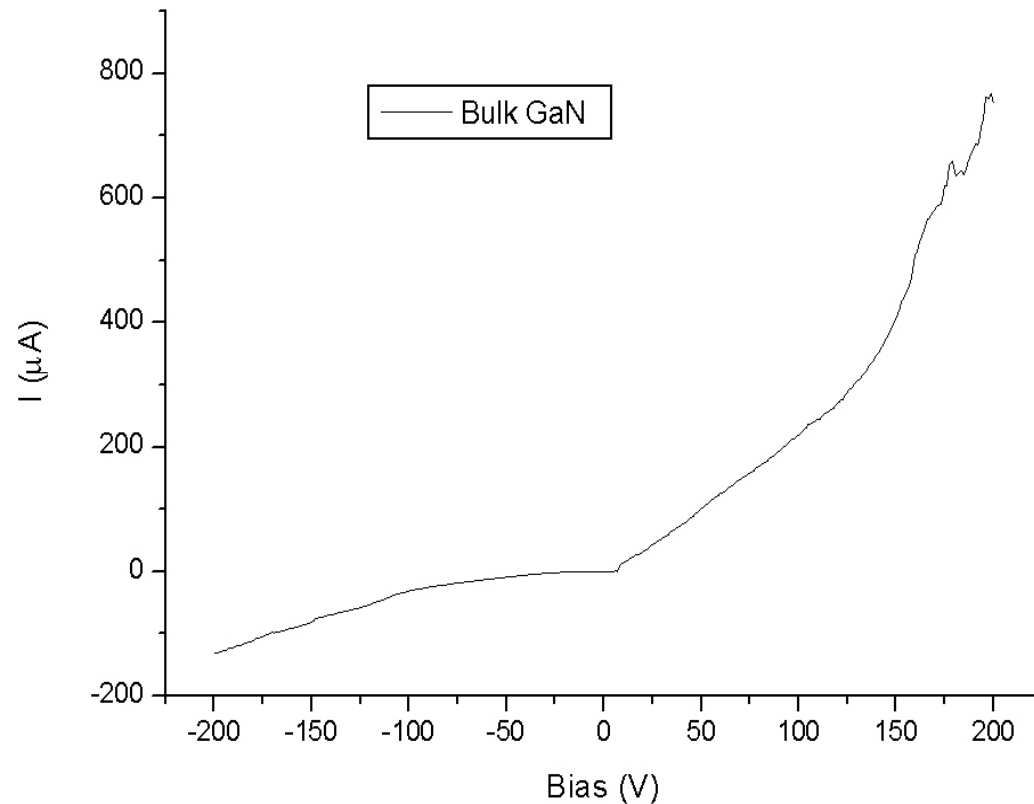


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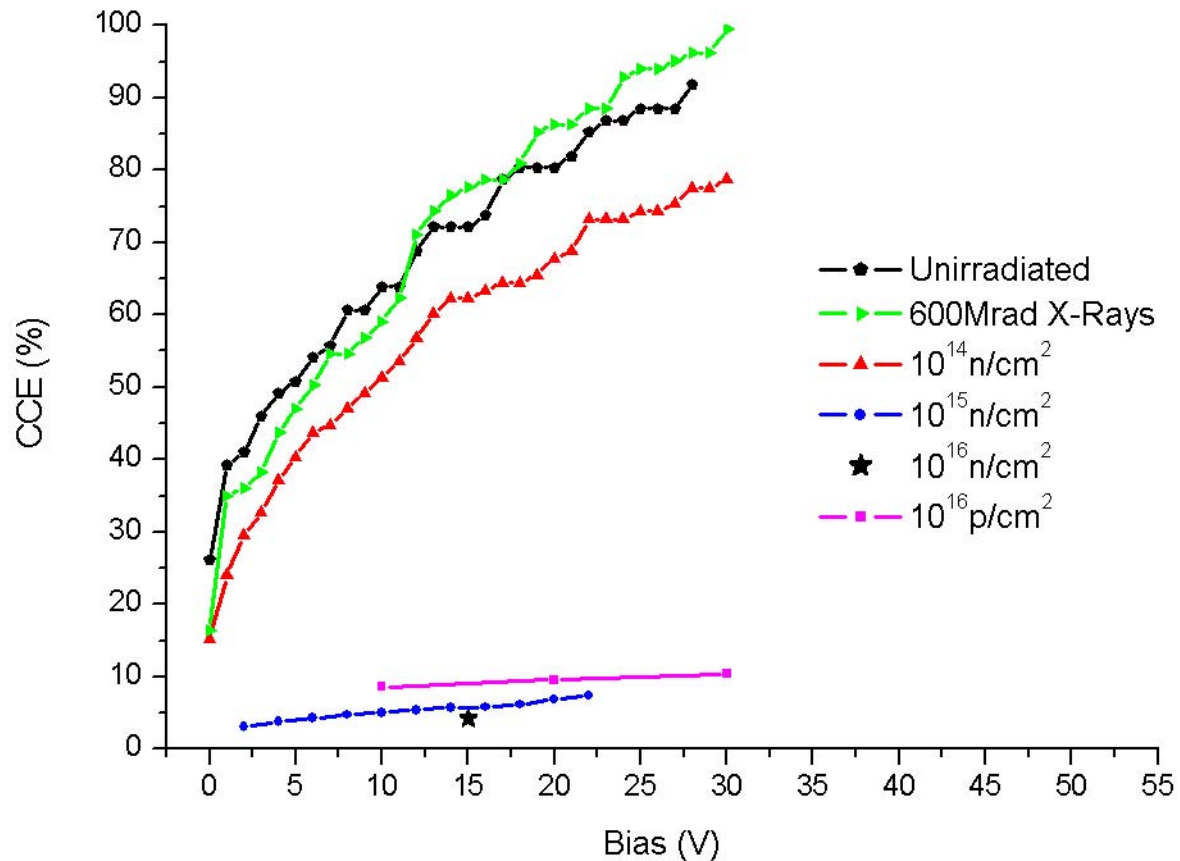
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I-V characteristic of bulk GaN

Poor non-symmetric leakage values due to inhomogeneous crystal



CCE of SI epitaxial GaN



Analysis and Summary of GaN

➤ SI epitaxial GaN

- Non-linear increase in leakage current with fluence
 - has been observed in other widegap materials
- CCE modification at high fluences
 - ~5 % for 10^{16} cm⁻² protons and neutrons
 - could be improved by cooling?

➤ Bulk GaN

- Diode fabricated. High leakage current. Could be explained by its low resistivity + high density of defects
- CCE measurements to come

Conclusions and Future Work

- Bulk SiC reasonably promising detector material
- Demonstrated potential of SI GaN for room temp ionising radiation detectors
- Fabricated bulk GaN devices. CCE measurements to be carried out
- Have 12 μ m epitaxial GaN. Device fabrication is ongoing

Background and Motivation

➤ Harsh environments present a severe challenge for designers of semiconductor devices and electronics

e.g. electronics for use in space

critical systems for nuclear reactors

position sensitive detectors for particle beams

➤ Radiation induced defects within s/c lead to

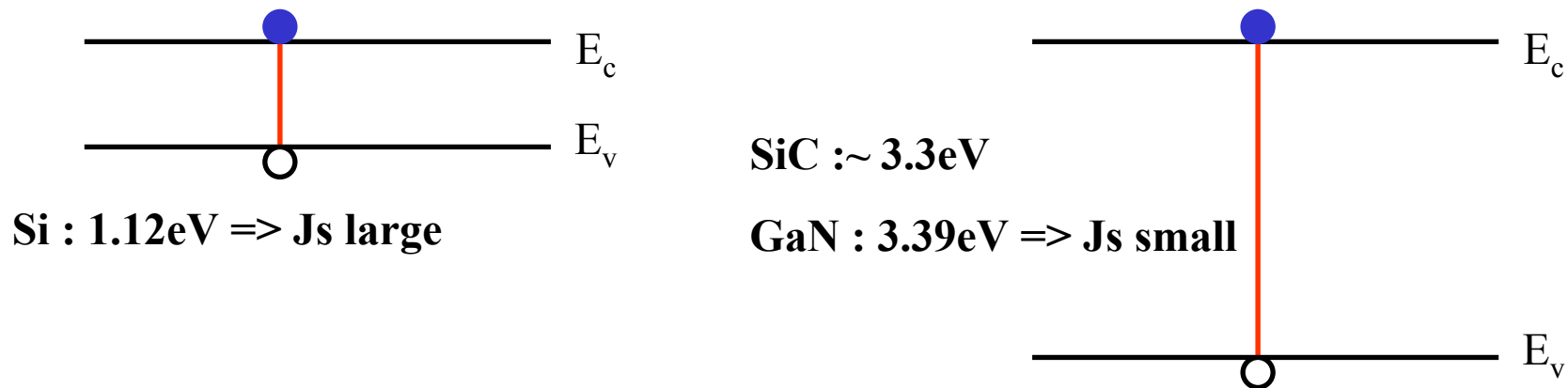
- enhanced generation /recombination currents (J_s)

- reduced charge collection signals

- drift in the operating point

Wide Bandgap Materials

- Wide bandgap materials are often advertised as being radiation hard

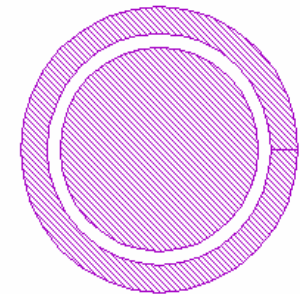
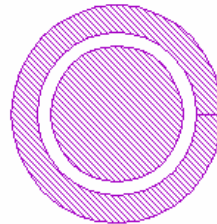
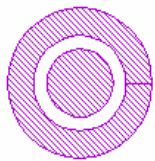


- This arises because the large energy difference between any created defect levels and the conduction or valence band edges reduces the transition probabilities significantly. Hence any J_s currents that are usually a problem with radiation damage are minimised

Fabrication (SiC)

➤ Pad/Guard ring structures fabricated on the 2 different SiC materials using photolithography techniques

- 100nm Ti Schottky front contact
- 100nm Ni ohmic back contact
- Si_3N_4 passivation of remaining free SiC surfaces (Okmetic SiC)



Pad Diameter 250-750 μm

50 μm between pad +GR

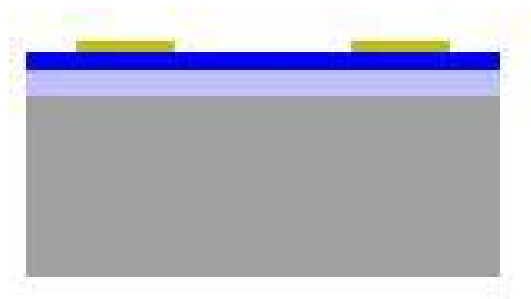
100 μm thick GR

Fabrication (GaN)

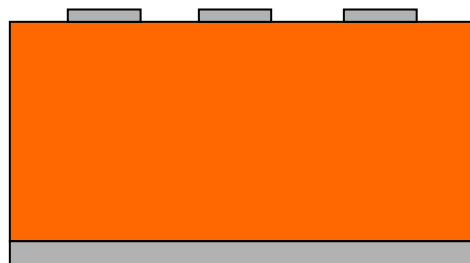
➤ Pad/Guard ring structures for both the Bulk GaN and SI epitaxial GaN using photolithography

- SI epitaxial GaN => 100nm Au Schottky contact

- Bulk GaN => 80nm Pd for both front and back Schottky contacts



- 100nm Au
- 2-2.5µm capping layer
- 2µm n* buffer layer
- Sapphire (0001) plane



- Bulk GaN ~ 450µm thick
- 80nm Pd